

US00D505969S

(12) **United States Design Patent**
Yeung

(10) **Patent No.:** **US D505,969 S**

(45) **Date of Patent:** **** Jun. 7, 2005**

(54) **MASK**

(75) **Inventor:** **Wa Sang Yeung, Kowloon (HK)**

(73) **Assignee:** **Eastcolight (Hong Kong) Ltd., Lai Chi Kok (HK)**

(**) **Term:** **14 Years**

(21) **Appl. No.:** **29/201,800**

(22) **Filed:** **Mar. 19, 2004**

(51) **LOC (8) Cl.** **16-06**

(52) **U.S. Cl.** **D16/309; D16/312; D21/517**

(58) **Field of Search** **D16/101, 300-330; D29/109-110; D24/110.2; D14/372, 496, 371; D21/324, 517; D26/38-39; 351/41, 44, 158; 2/426, 425, 909, 447, 444**

(56) **References Cited**

U.S. PATENT DOCUMENTS

4,729,132 A	*	3/1988	Fierro	2/909
D352,046 S	*	11/1994	Kataoka	D16/309
5,371,555 A	*	12/1994	Nagel	2/444
D363,482 S	*	10/1995	Robinson et al.	D14/372
5,724,119 A	*	3/1998	Leight	351/158

D397,334 S	*	8/1998	Larian	D14/372
6,009,563 A	*	1/2000	Swanson et al.	2/425
D439,266 S	*	3/2001	Rose	D16/309
D440,967 S	*	4/2001	Jung	D14/372
6,511,177 B1	*	1/2003	Hall et al.	351/158
2004/0160572 A1	*	8/2004	Jannard et al.	351/158

* cited by examiner

Primary Examiner—Raphael Barkai

(74) *Attorney, Agent, or Firm*—Intellectual Property Law Group LLP; Otto O. Lee; Juneko Jackson

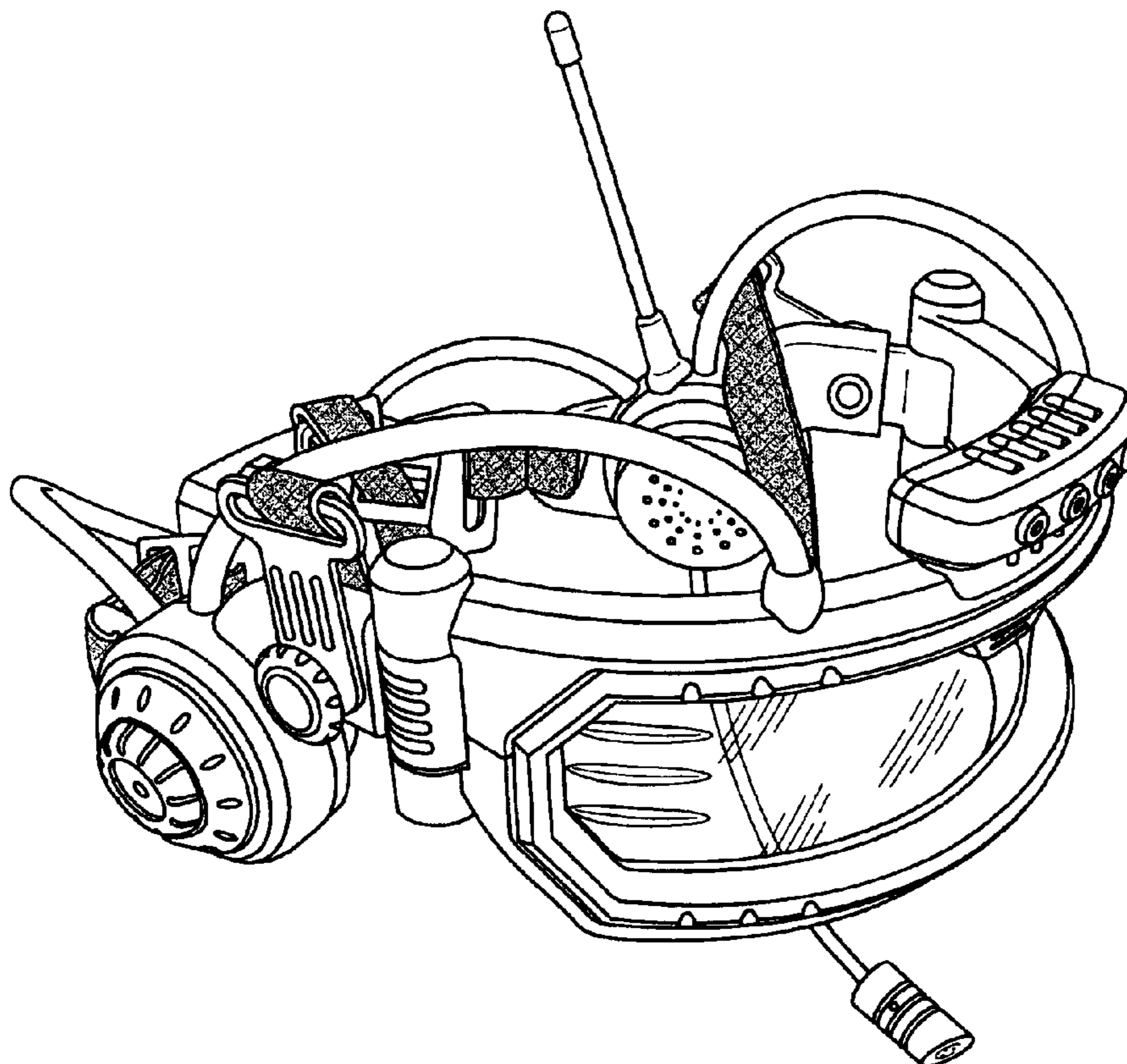
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask embodying my design;
 FIG. 2 is an elevational front view thereof;
 FIG. 3 is an elevational rear view thereof;
 FIG. 4 is a right side elevational view thereof;
 FIG. 5 is a left side elevational view thereof;
 FIG. 6 is a top plan view thereof; and,
 FIG. 7 is a bottom plan view thereof.

1 Claim, 4 Drawing Sheets



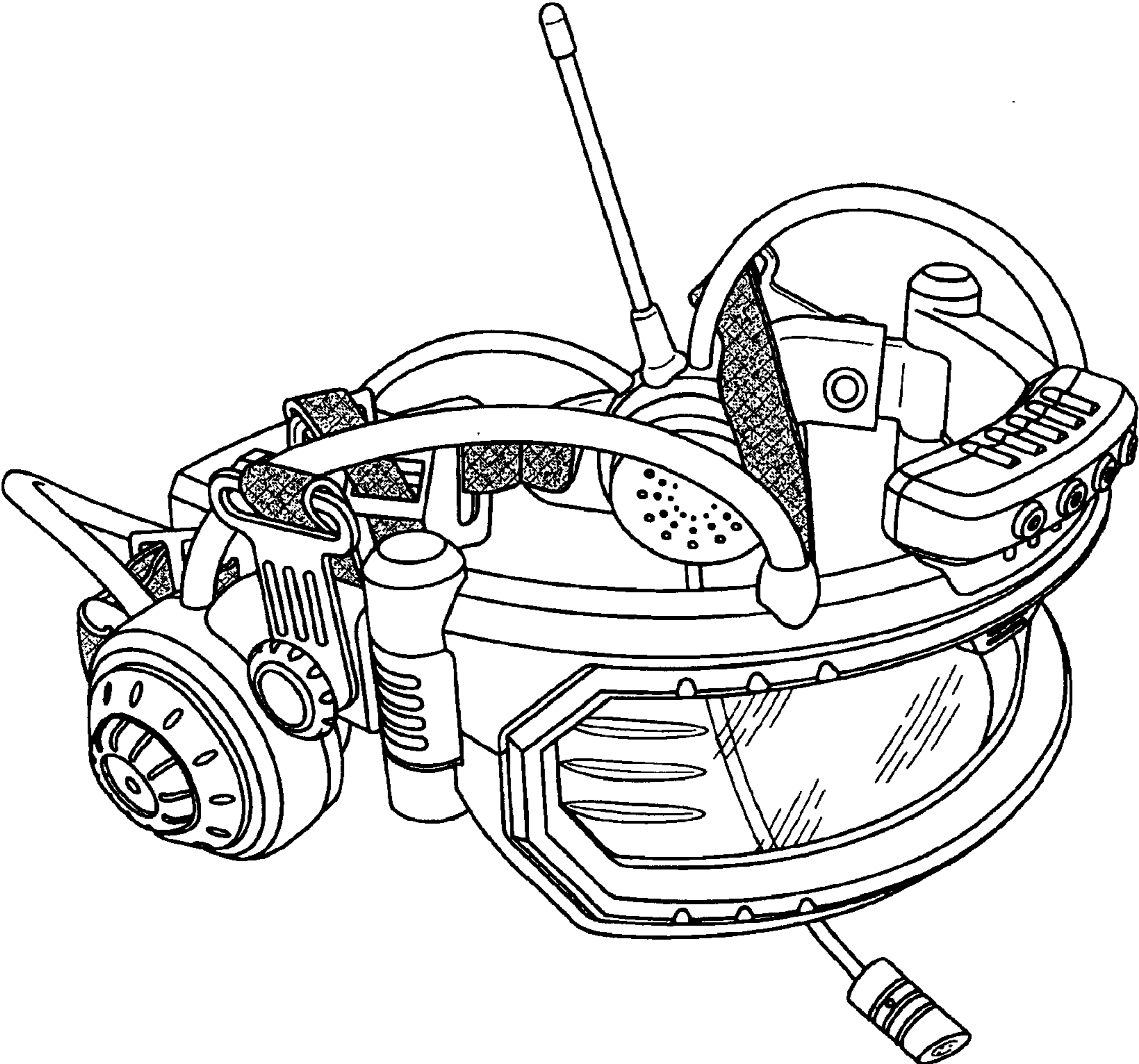


FIG. 1

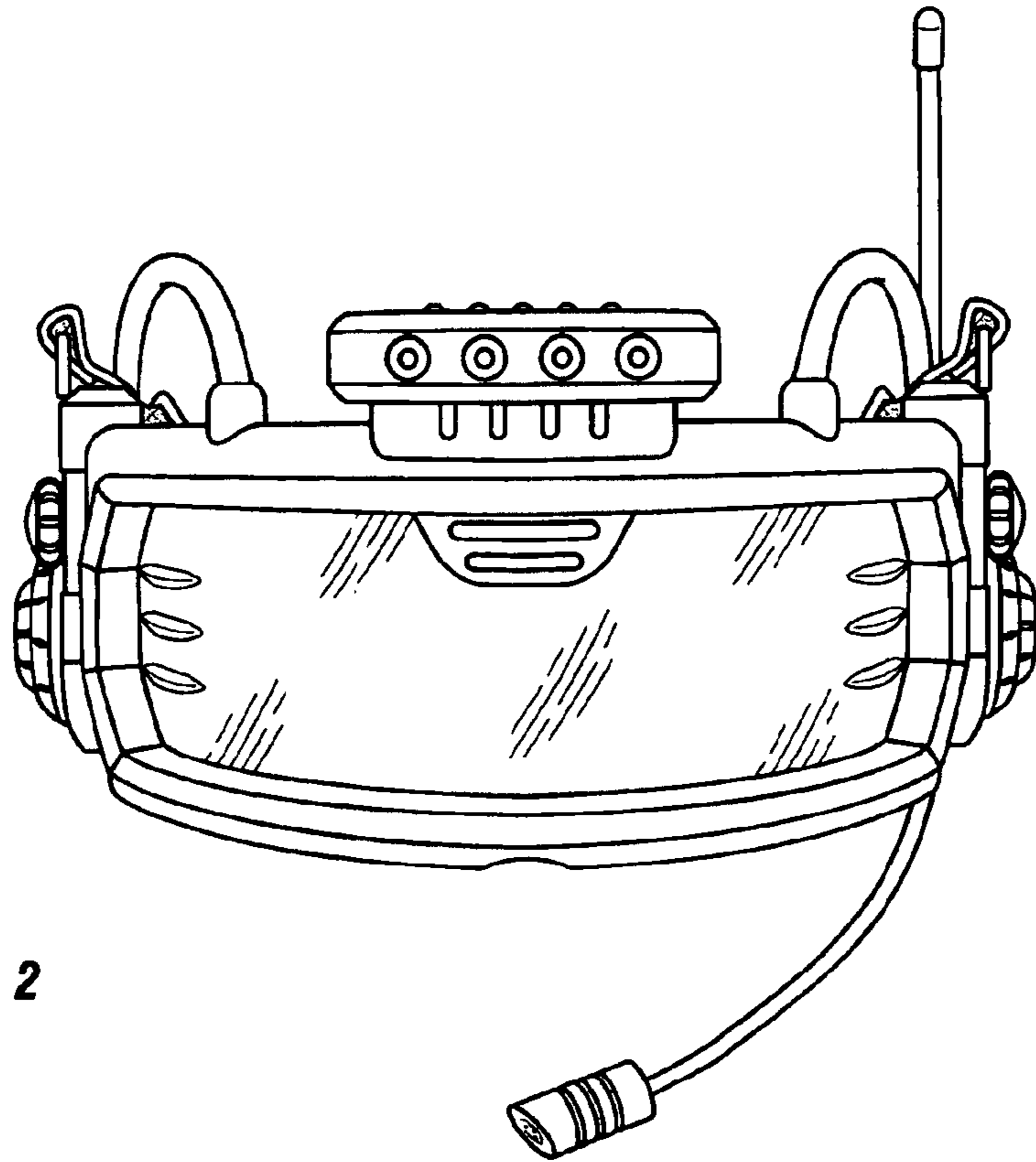


FIG. 2

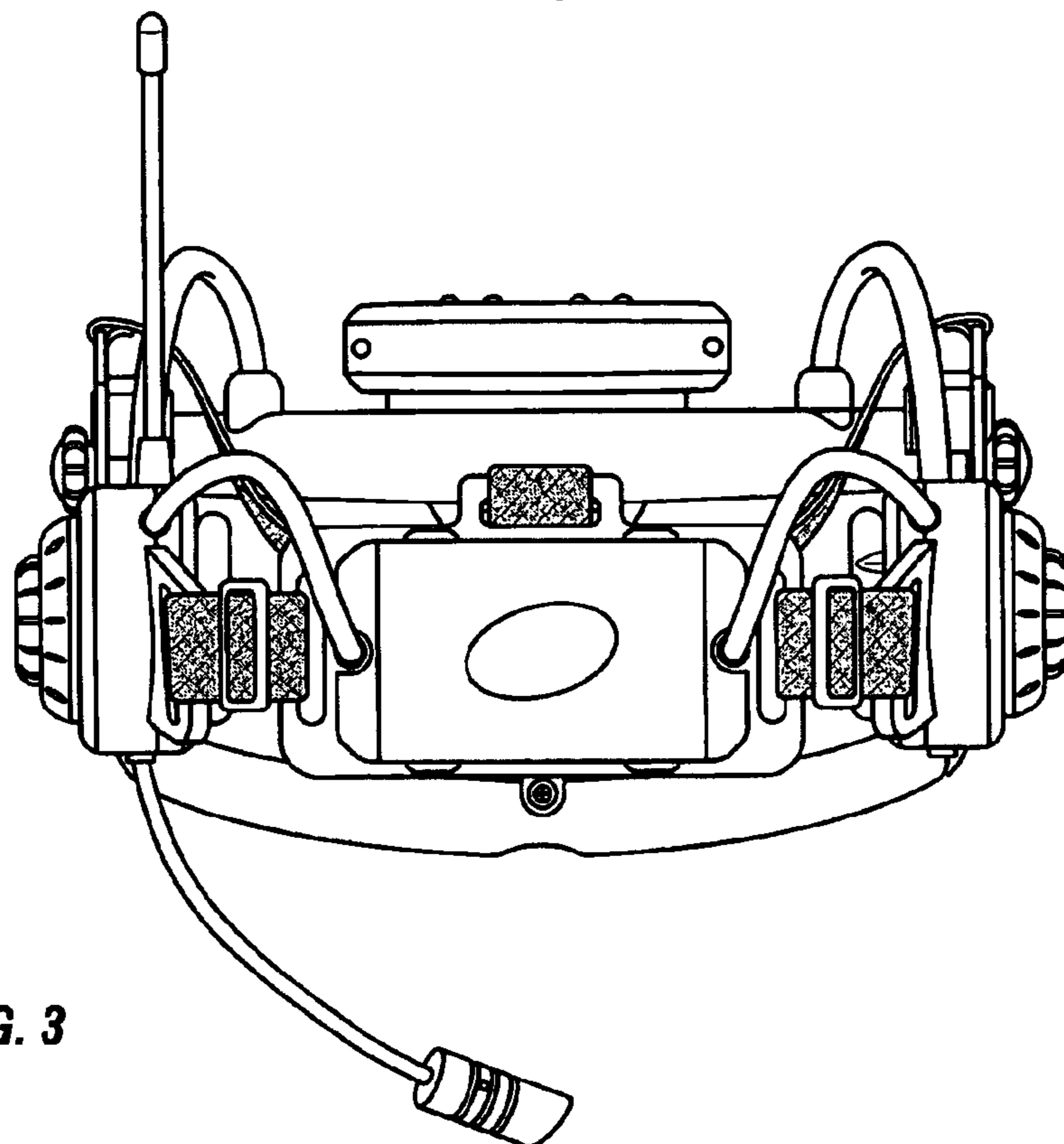


FIG. 3

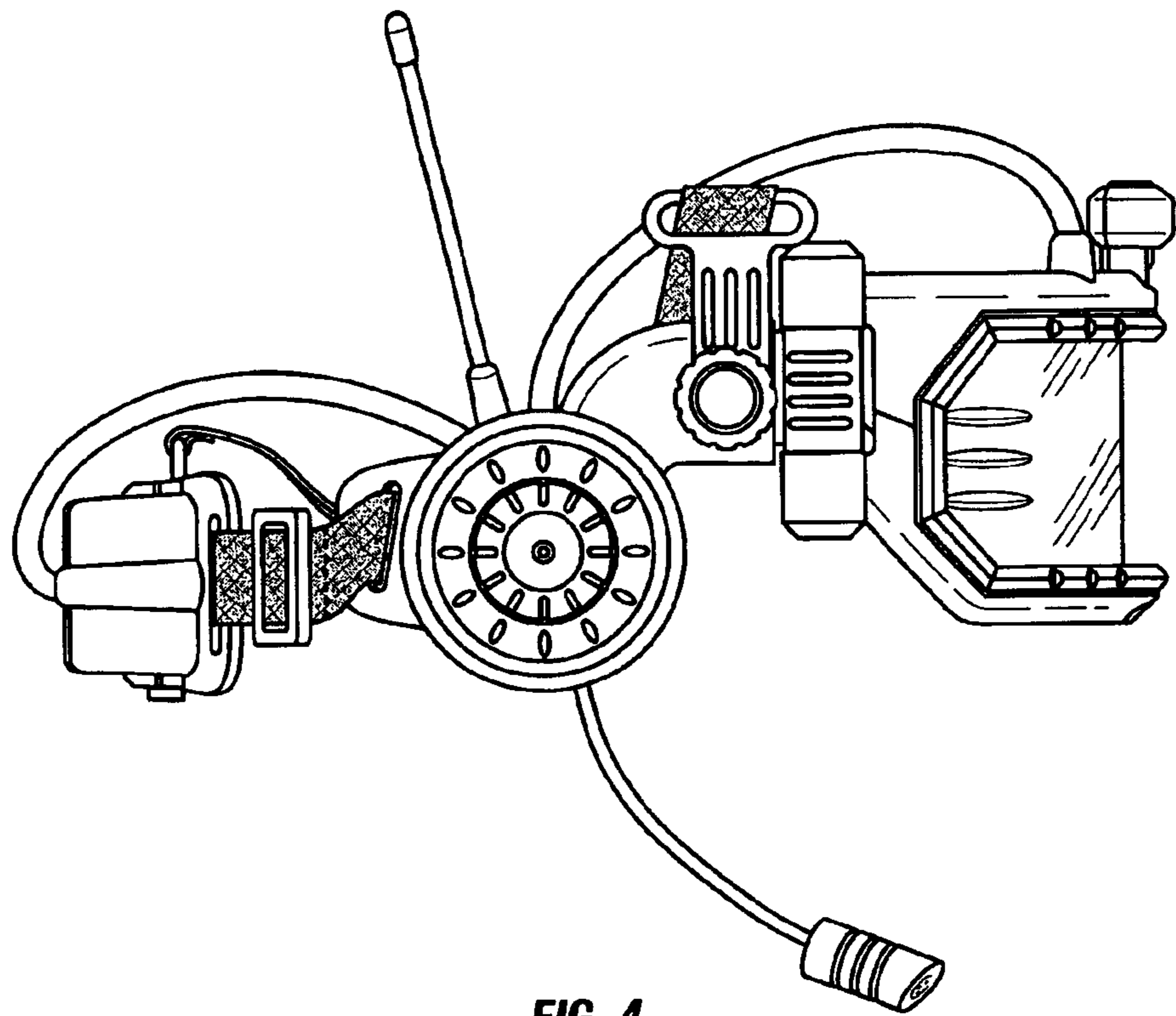


FIG. 4

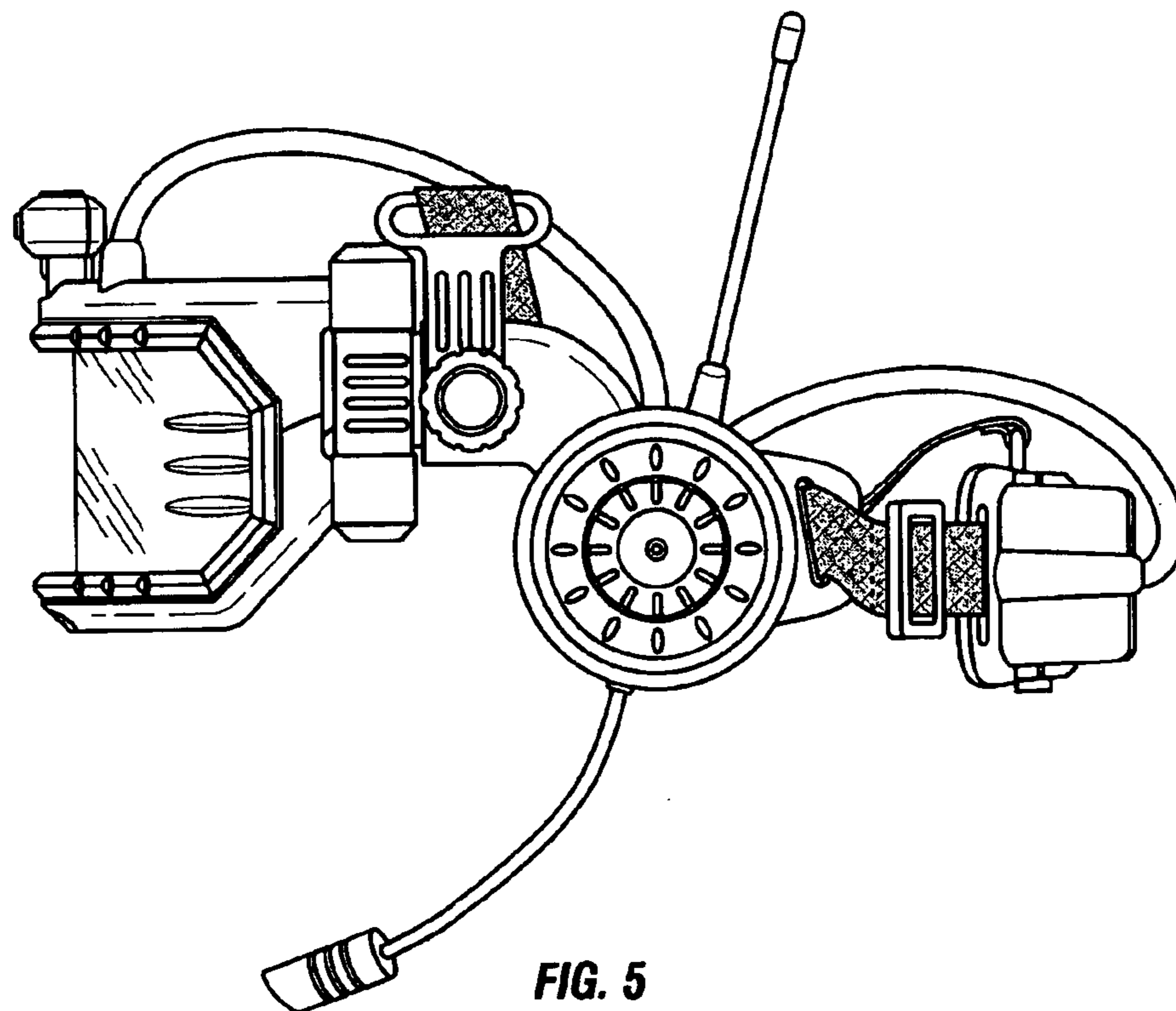


FIG. 5

